

A Facile Hybrid Approach to High-performance Broadband Antireflective Thin films
with Humidity Resistance as well as Mechanical Robustness

Tong Li^{a,b} and Junhui He^{a,*}

^a Functional Nanomaterials Laboratory, Center for Micro/Nanomaterials and Technology, and Key Laboratory of Photochemical Conversion and Optoelectronic Materials, Technical Institute of Physics and Chemistry, Chinese Academy of Sciences, Zhongguancundonglu 29, Haidianqu, Beijing 100190, China.

^b University of Chinese Academy of Sciences, Beijing 100049, China.

* Corresponding author. Fax: +86 10 82543535. E-mail address: jhhe@mail.ipc.ac.cn.

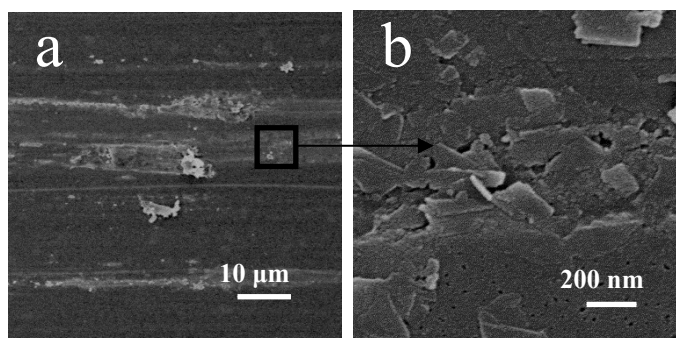


Figure S1. Low (a) and high (b) magnification SEM images of M4T6 hybrid thin film after 4H pencil hardness test.

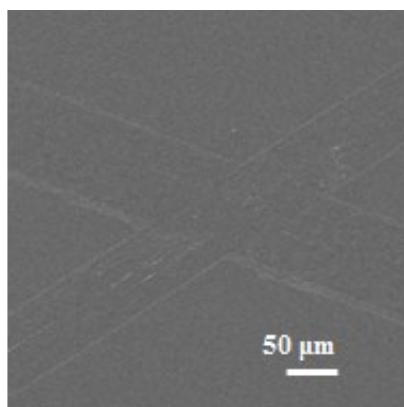


Figure S2. SEM image of M4T6 hybrid thin film after adhesion test.